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#7/Amet A 3-11-03

PATENT Customer No. 22,852 Attorney Docket No. 08244.0032

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Sung-chan PARK et al.) Group Art Unit: 2813
Application No.: 09/998,303) Examiner: T. Nguyen
Filed: December 3, 2001	C-5
For: METHOD FOR FORMING CONTACT HOLD AND SPACER OF SEMICONDUCTOR DEVICE	Group Art Unit: 2813 Examiner: T. Nguyen PEC-5 2002 RECEIVED
Commissioner for Patents Washington, DC 20231	Entre Carlo

<u>AMENDMENT</u>

In reply to the Office Action dated July 31, 2002, the period for reply having been extended for one month to December 2, 2002 (November 30, 2002 being a Saturday) by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE CLAIMS:

Sir:

Please cancel claims 10-20 without prejudice or disclaimer of the subject matter thereof, and amend claims 1, 6 and 8 as follows:

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1. (Amended) A method for forming contact openings between bit line patterns, the method comprising the steps of: